

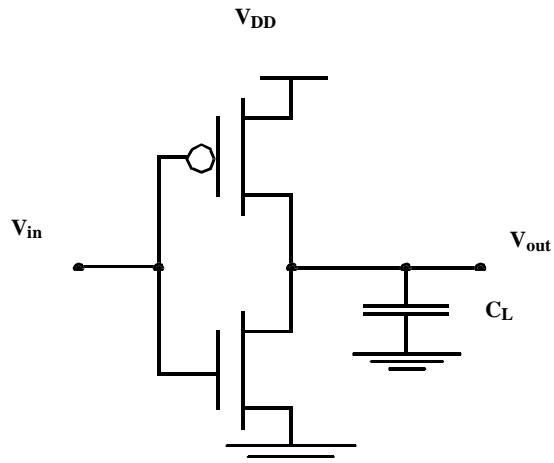
CMOS INVERTER

The CMOS Inverter – Static Model

Outline

- First Glance
- Digital Gate Characterization
- Static Behavior (Robustness)
 - VTC
 - Switching Threshold
 - Noise Margins

The CMOS Inverter: A First Glance

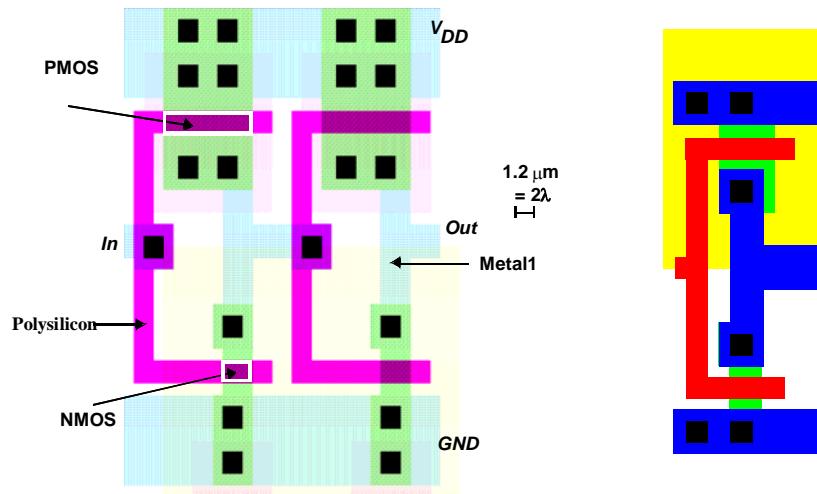


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CMOS Inverters (1)

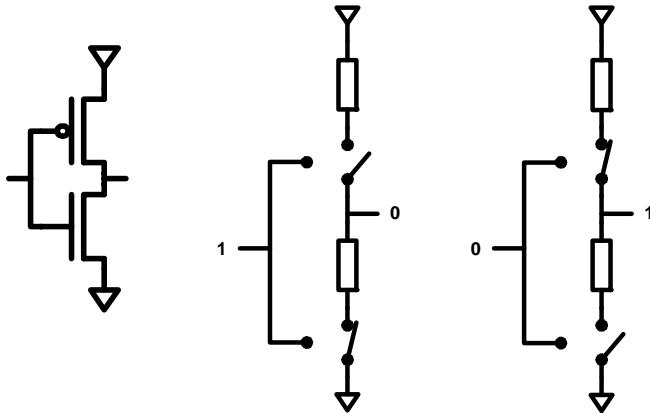


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CMOS Inverter Operation Principle



$$V_{OH} = V_{DD} \quad V_{OL} = 0$$

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Digital Gate Fundamental Parameters

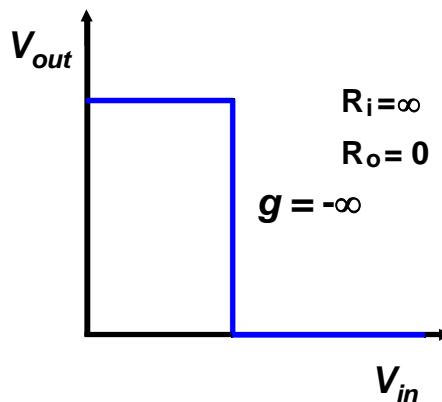
- **Functionality**
- **Reliability, Robustness**
- **Area**
- **Performance**
 - **Speed (delay)**
 - **Power Consumption**
 - **Energy**

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The Ideal Inverter

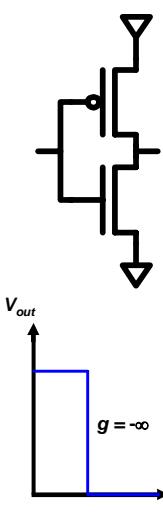


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Static CMOS Properties



Basic inverter belongs to class of **static circuits**: output always connected to either V_{DD} or V_{SS} . **Not ideal but:**

- Rail to rail voltage swing
- Ratio less design
- Low output impedance
- Extremely high input impedance
- No static power dissipation
- Good noise properties/margins

Exercise: prioritize the list above

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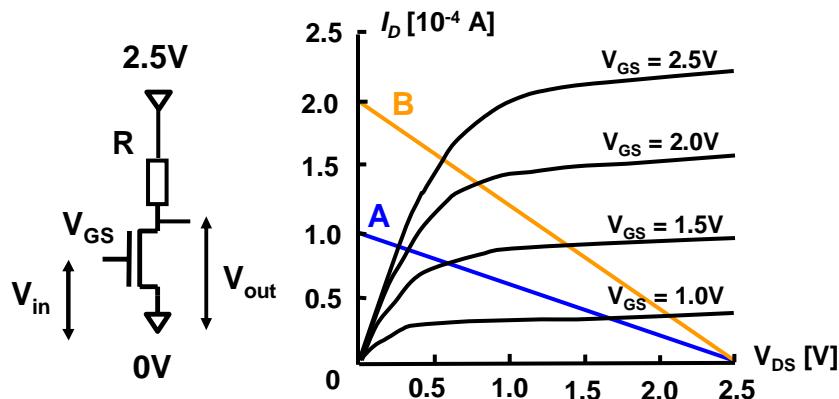
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Voltage Transfer Characteristic (VTC)



Load Line (Ckt Theory)



Exercise:

The blue load line A corresponds to $R =$

The orange load line B corresponds to $R =$

With load line A and $V_{GS} = 1V$, $V_{out} =$

Draw a graph $V_{out}(V_{in})$ for load line A and B

PMOS Load Lines

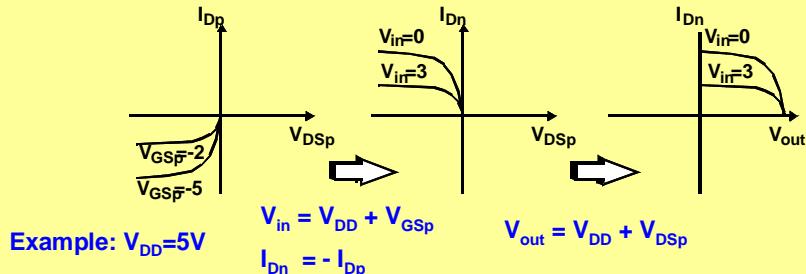
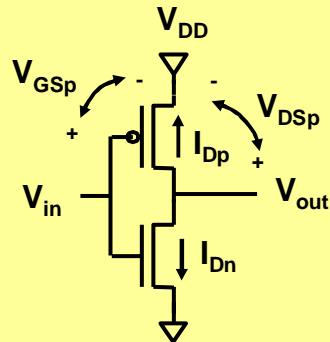
Goal: Combine I_{Dn} and I_{Dp} in one graph

Kirchoff:

$$V_{in} = V_{DD} + V_{GSp}$$

$$I_{Dn} = -I_{Dp}$$

$$V_{out} = V_{DD} + V_{DSP}$$

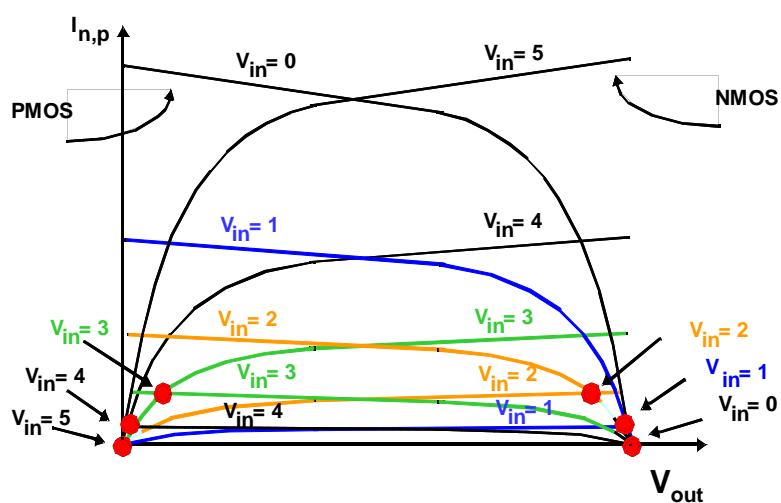


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CMOS Inverter Load Characteristics

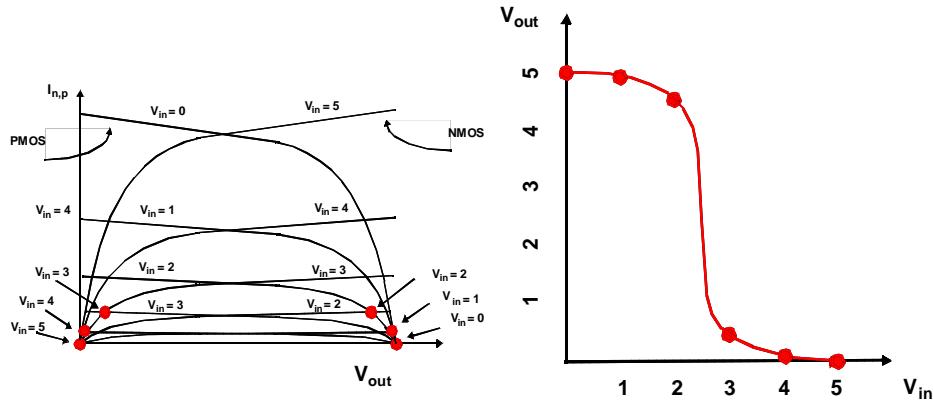


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CMOS Inverter VTC



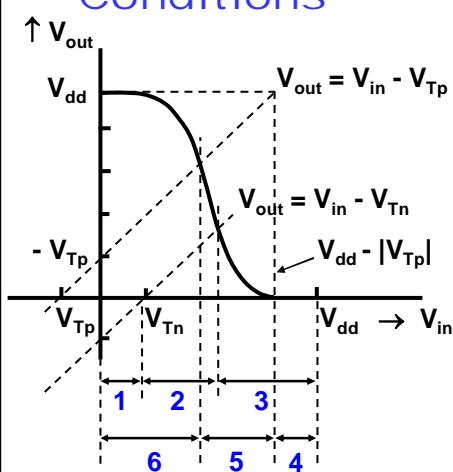
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Operating Conditions

Need to know for proper dimensioning, analysis of noise margin, etc.



NMOS

- 1 $V_{in} = V_{GS} < V_{tN} \Rightarrow \text{off}$
- 2 $V_{out} > V_{in} - V_{tN}$
 $V_{DS} > V_{GS} - V_{tN}$
 $V_{GD} < V_{tN} \Rightarrow \text{saturation}$
- 3 $V_{out} < V_{in} - V_{tN} \Rightarrow \text{resistive}$

PMOS

- 4 $V_{in} > V_{DD} + V_{tp} \Rightarrow \text{off}$
- 5 $V_{out} < V_{in} - V_{tp} \Rightarrow \text{saturation}$
- 6 $V_{out} > V_{in} - V_{tp} \Rightarrow \text{resistive}$

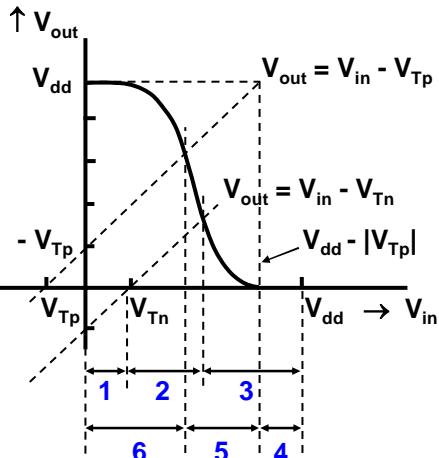
Exercise: check results for PMOS

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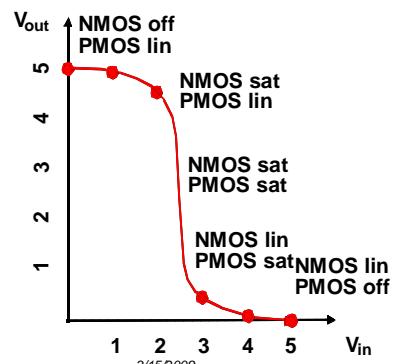
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Operating Conditions



NMOS	1 off
2 saturation	
3 resistive	
PMOS	4 off
5 saturation	
6 resistive	



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Inverter Static Behavior

- Regeneration
- Noise margins
- Delay metrics

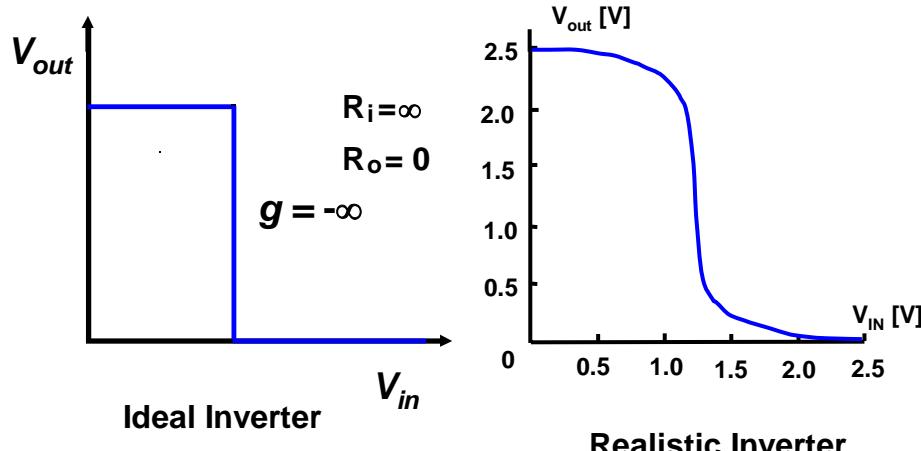


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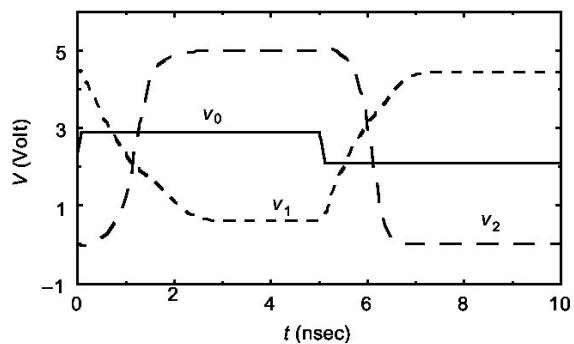
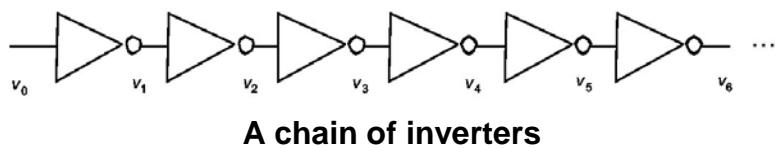
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The Realistic Inverter



The Regenerative Property

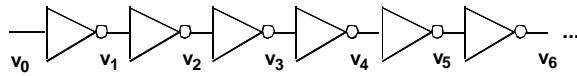


■ **Regenerative Property:** ability to regenerate (repair) a weak signal in a chain of gates

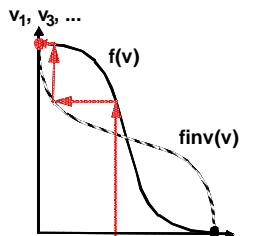


The regenerative property

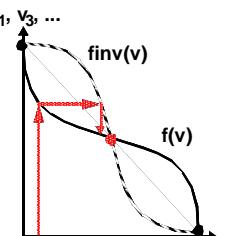
The Regenerative Property (2)



(a) A chain of inverters.

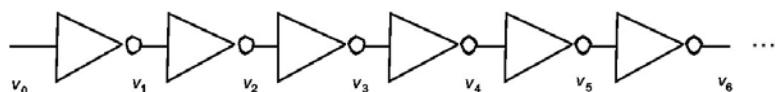


(b) Regenerative gate



(c) Non-regenerative gate

The regenerative Property (3)



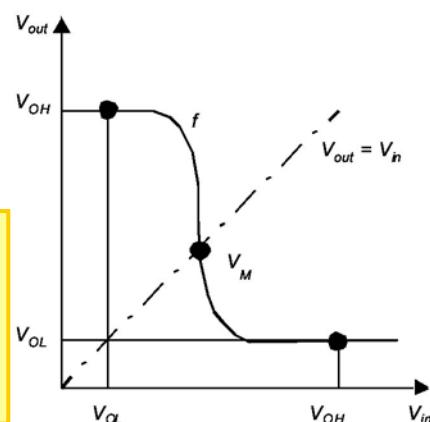
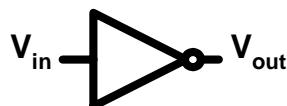
Exercise: what is the output voltage of a chain of 4 inverters with a piece-wise linear VTC passing through (0, 10), (3,7), (7,1) and (10,0) [Volt], as the result of an input voltage of 6 [Volt].

Exercise: discuss the behavior for an input of 5 [Volt]

Inverter Switching Threshold

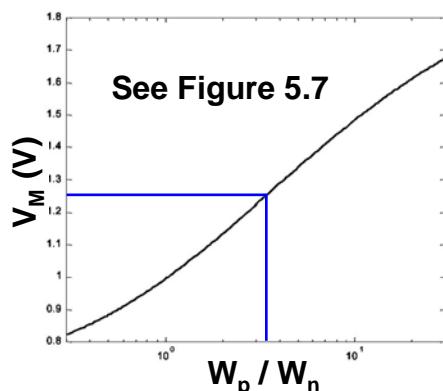
- Not the device threshold $V_m = f(R_{onn}, R_{onp})$

- Point of $V_{in} = V_{out}$



■ Try to set W_n, L_n, W_p, L_p
so that VTC is symmetric
as this will improve noise
margins
optimize NMOS-PMOS ratio

Simulated Gate Switching Threshold



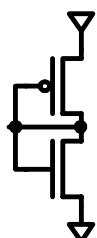
Electrical Design Rule
 $W_p \approx 2.5 W_n$

- Assumes $L_p = L_n$
- Should be applied consistently

- Symmetrical VTC $\Rightarrow V_m \approx \frac{1}{2} V_{DD} \Rightarrow W_p/W_n \approx \boxed{}$
- In practice: somewhat smaller
- Why?

Inverter Switching Threshold Analytical Derivation

- V_M is V_{in} such that $V_{in} = V_{out}$
- $V_{DS} = V_{GS} \Leftrightarrow V_{GD} = 0 \Rightarrow \text{saturation}$
 - Assume $V_{DSAT} < V_M - V_T$
 - (velocity saturation)
 - Ignore channel length modulation
- V_M follows from
 - $I_{DSATn}(V_M) = -I_{DSATp}(V_M)$



 § 5.3.1

Inverter Switching Threshold Analytical Derivation (ctd)

$$I_{DSATn}(V_M) = -I_{DSATp}(V_M) \quad I_D = kV_{DSAT}(V_{GS} - V_T - V_{DSAT}/2)$$

$$\Leftrightarrow k_n V_{DSATn}(V_M - V_{Tn} - V_{DSATn}/2) = -k_p V_{DSATp}(V_M - V_{DD} - V_{Tp} - V_{DSATp}/2)$$

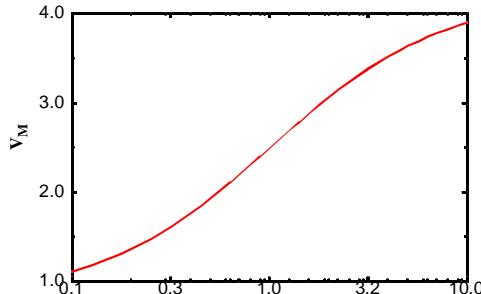
$$\Leftrightarrow \frac{k_p}{k_n} = \frac{-V_{DSATn}(V_M - V_{Tn} - V_{DSATn}/2)}{V_{DSATp}(V_M - V_{DD} - V_{Tp} - V_{DSATp}/2)} \quad k = \frac{W}{L} k'$$

$$\Rightarrow \frac{(W/L)_p}{(W/L)_n} = \left| \frac{k_n V_{DSATn}(V_M - V_{Tn} - V_{DSATn}/2)}{k_p V_{DSATp}(V_M - V_{DD} - V_{Tp} - V_{DSATp}/2)} \right|$$

- See Example 5.1:
- $(W/L)_p = 3.5 (W/L)_n$ for typical conditions and $V_M = \frac{1}{2} V_{DD}$
- Usually: $L_n = L_p$

Gate Switching Threshold w/o Velocity Saturation

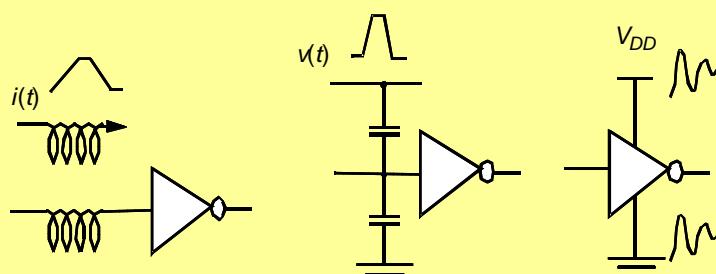
- Long channel approximation
- Applicable with low V_{DD}



Exercise (Problem 5.1):
derive V_M for long-channel approximation as shown below

$$V_M = \frac{r(V_{DD} - V_{Tp} + V_{Tn})}{1+r} \text{ with } r = \sqrt{\frac{-k_p}{k_n}}$$

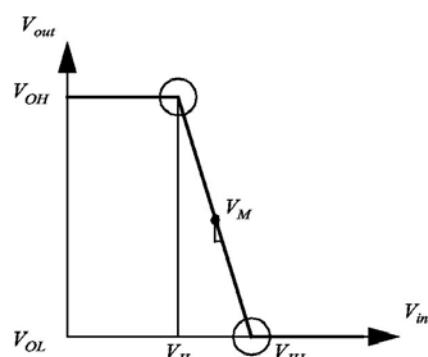
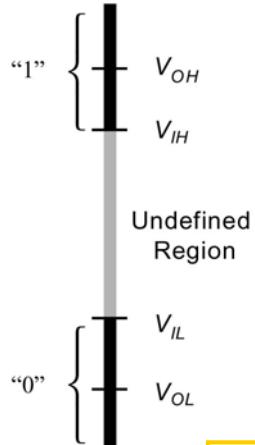
Noise in Digital Integrated Circuits



(a) Inductive coupling (b) Capacitive coupling (c) Power and ground noise

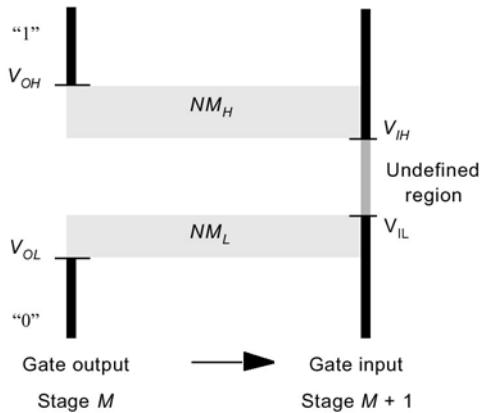
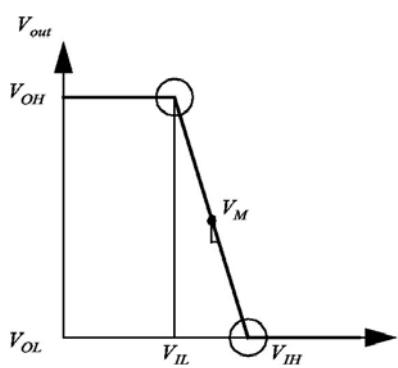
- Study behavior of static CMOS Gates with noisy signals

Noise Margins



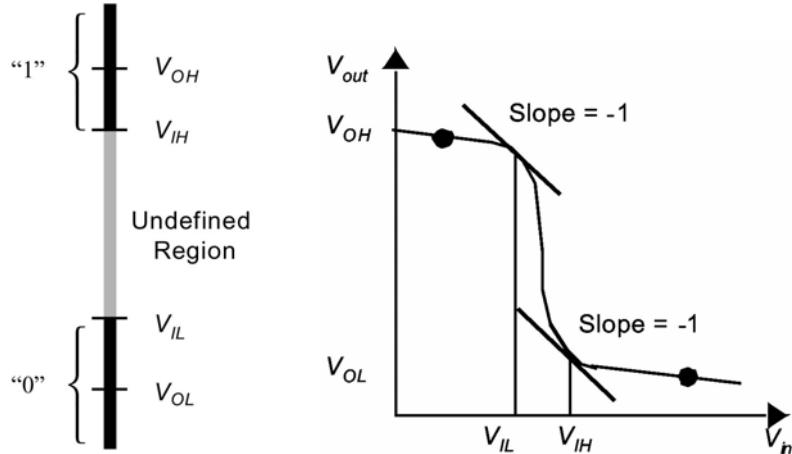
- **V_{OL} = Output Low Voltage**
- **V_{IL} = Input Low Voltage**
- **V_{OH}, V_{IH} = ...**

Noise Margins



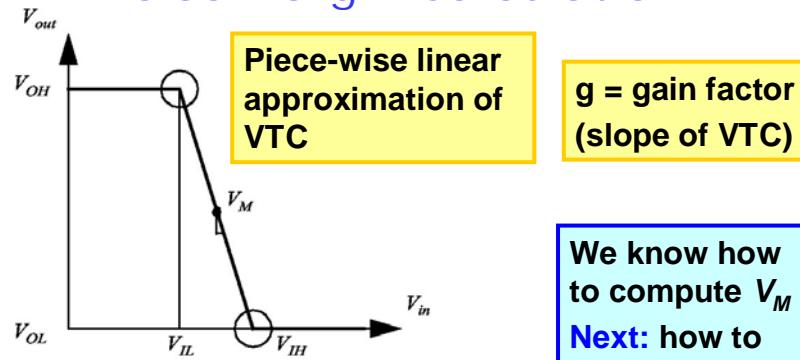
- **NM_H = V_{OH} - V_{IH} = High Noise Margin**
- **NM_L = V_{IL} - V_{OL} = Low Noise Margin**

Noise Margin for Realistic Gates



Exercise: explain significance of slope = -1 for noise margin

Noise Margin Calculation



$$V_{IH} - V_{IL} = -\frac{(V_{OH} - V_{OL})}{g} = \frac{-V_{DD}}{g}$$

$$V_{IH} = V_M - \frac{V_M}{g} \quad V_{IL} = V_M + \frac{V_{DD} - V_M}{g}$$

$$NM_H = V_{DD} - V_{IH} \quad NM_L = V_{IL}$$

Noise Margin Calculation (2)

- Approximate g as the slope in V_{out} vs. V_{in} at $V_{in} = V_M$

$$k_n V_{DSATn} (V_{in} - V_{Tn} - V_{DSATn}/2)(1 + \lambda_n V_{out}) +$$

$$k_p V_{DSATp} (V_{in} - V_{DD} - V_{Tp} - V_{DSATp}/2)(1 + \lambda_p V_{out} - \lambda_p V_{DD}) = 0$$

$$g = \frac{dV_{out}}{dV_{in}} \Big|_{V_{in}=V_M} \approx \frac{1+r}{(V_M - V_T - V_{DSATp}/2)(\lambda_n - \lambda_p)} \quad r = \frac{k_p V_{DSATp}}{k_n V_{DSATn}}$$

- Mostly determined by technology

- See example 5.2

■ Exercise: verify calculation

■ Exercise: explain why we add channel length modulation to the I_D expressions (we did not do this to determine V_M)

CMOS INVERTER dynamic behavior (performance)

- Capacitances
- (Dis)charge times
- Delay



■ Before: propagation delay analysis

$$t_p \approx 0.69 \times \frac{3}{4} \frac{V_{DD}}{I_{DSAT}} \left(1 - \frac{5}{6} \lambda V_{DD} \right) C_L$$

■ Next: propagation delay from a design perspective
inverter sizing



Reducing t_p

$$\left. \begin{aligned} t_{pHL} &\approx 0.69 \times \frac{3}{4} \frac{V_{DD}}{I_{DSATn}} \left(1 - \frac{5}{6} \lambda V_{DD} \right) C_L \\ I_{DSAT} &= k' \frac{W}{L} \left[(V_{GS} - V_T) V_{DSAT} - \frac{1}{2} V_{DSAT}^2 \right] \end{aligned} \right\} \lambda = 0$$

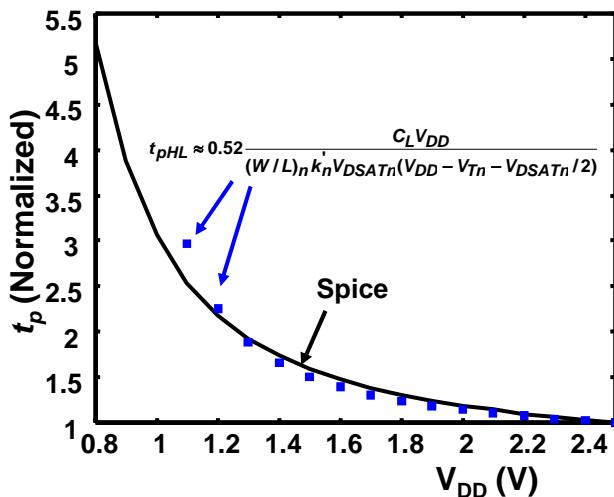
$$t_{pHL} \approx 0.52 \frac{C_L V_{DD}}{(W/L)_n k_n V_{DSATn} (V_{DD} - V_{Tn} - V_{DSATn}/2)}$$

Propagation Delay t_p can be reduced by

- Increasing V_{DD} (until $V_{DD} \gg V_T + V_{DSAT}/2$)
- Increasing W
- Reducing C_L

Delay as a function of V_{DD}

Fg.5.17



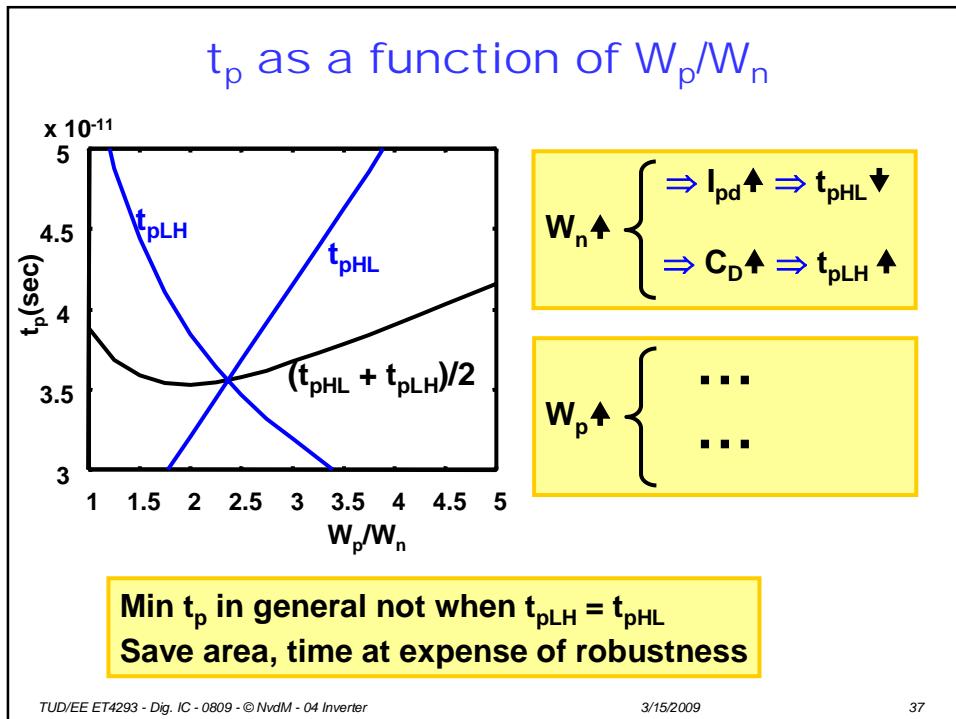
Sizing

Propagation Delay t_p can be reduced by

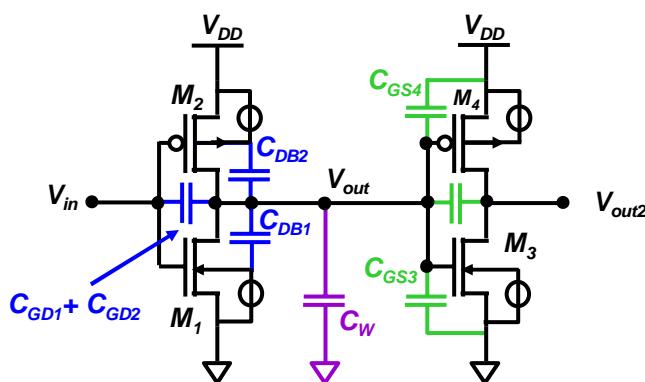
- Increasing V_{DD} (until $V_{DD} \gg V_T + V_{DSAT}/2$)
- Increasing W
- Reducing C_L

$$t_{pHL} = 0.52 \frac{C_L V_{DD}}{(W/L)_n k_n V_{DSATn} (V_{DD} - V_{Tn} - V_{DSATn}/2)} \propto \frac{C_L}{W}$$

- C_L can be reduced by good layout design
- But part of C_L depends on W !



Intrinsic vs Extrinsic vs Parasitic Load Cap



- $C_{int} = C_{DB1} + C_{DB2} + 2(C_{GD1} + C_{GD2})$ Intrinsic load
- $C_{ext} = C_{GS3} + C_{GS4} + C_{GD3} + C_{GD4}$ Extrinsic / fan-out load
- $C_{par} = C_w$ Parasitic load

Isolated Inverter Sizing

$$t_p = 0.69 R_{eq} (C_{int} + C_{ext}) = 0.69 R_{eq} C_{int} \left(1 + \frac{C_{ext}}{C_{int}}\right)$$

Assume C_{par} can be ignored or its effect can be absorbed in other C

R_o : resistance of minimum size inverter
(assume proper $\beta = W_p / W_n$ ratio)

C_o : intrinsic load (output, drain) cap of min. size inverter

$t_{p0} = 0.69 R_o C_o$:
intrinsic or unloaded delay

basic time constant for technology

minimum delay possible in technology given V_{DD}

S: sizing factor for W_n , W_p of driving inverter
 $W_n = S W_{min}$, $W_p = S \beta W_{min}$

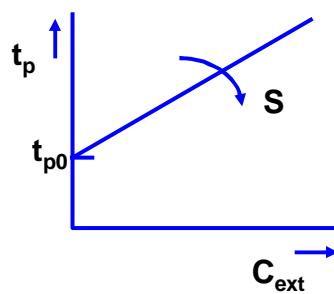
→ $R_{eq} = R_o/S$ $C_{int} = SC_o$

$$\Rightarrow t_p = t_{p0} \left(1 + \frac{C_{ext}}{SC_o}\right)$$

Isolated Inverter Sizing

$$t_p = t_{p0} \left(1 + \frac{C_{ext}}{SC_o}\right)$$

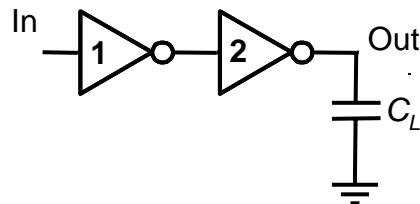
Increasing S reduces delay until $SC_o \gg C_{ext}$



Inverter Chain

Assume size of inverter 1 is fixed.

- ⌚ Increasing S of inverter 2 reduces t_p of inverter 2
- ⌚ But it increases t_p of inverter 1 (higher load cap)
- ⌚ Expect an optimum!



If C_L is given:

- How many stages are needed to minimize the delay?
- How to size the inverters?

Delay Formula

$$t_p = t_{p0} \left(1 + \frac{C_{ext}}{SC_0} \right) = t_{p0} \left(1 + \frac{f}{\gamma} \right)$$

C_{gin} input gate capacitance

$\gamma = C_{int}/C_{gin} = SC_0/C_{gin}$

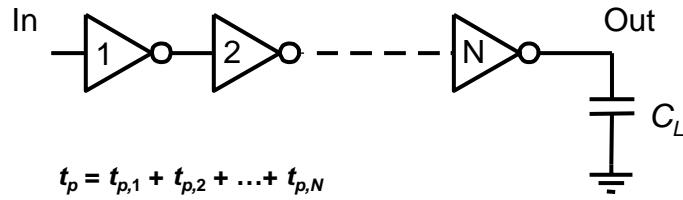
self loading coefficient

property of technology, typically $\gamma \approx 1$

$f = C_{ext}/C_{gin}$ effective fanout

$$\frac{f}{\gamma} = \frac{C_{ext}}{C_{gin}} \times \frac{C_{gin}}{SC_0}$$

Apply to Inverter Chain



$$t_{p,j} = t_{p0} \left(1 + \frac{f_j}{\gamma} \right) = t_{p0} \left(1 + \frac{C_{gin,j+1}}{\gamma C_{gin,j}} \right)$$

$$t_p = \sum_{j=1}^N t_{p,j} = t_{p0} \sum_{j=1}^N \left(1 + \frac{C_{gin,j+1}}{\gamma C_{gin,j}} \right), \quad C_{gin,N+1} = C_L$$

Apply to Inverter Chain

Delay equation has $N-1$ unknowns, $C_{gin,2} \dots C_{gin,N}$

$$t_p = \sum_{j=1}^N t_{p,j} = t_{p0} \sum_{j=1}^N \left(1 + \frac{C_{gin,j+1}}{\gamma C_{gin,j}} \right), \quad C_{gin,N+1} = C_L$$

Make $N-1$ partial derivatives for $C_{gin,j}$ zero for minimization:

$$\frac{\partial t_p}{\partial C_{gin,j}} = t_{p0} \left(\frac{1}{\gamma C_{gin,j-1}} - \frac{C_{gin,j+1}}{\gamma (C_{gin,j})^2} \right) = 0, \quad j = 2 \dots N-1$$

Size of each stage is geometric mean of 2 neighbors:

$$C_{gin,j} = \sqrt{C_{gin,j-1} \times C_{gin,j+1}}, \quad j = 2 \dots N-1$$

Optimal Tapering for Given N

Size of each stage is geometric mean of 2 neighbors:

$$C_{gin,j} = \sqrt{C_{gin,j-1} \times C_{gin,j+1}}, \quad j = 2 \dots N-1$$

$$\Rightarrow C_{gin,j}^2 = C_{gin,j-1} \times C_{gin,j+1}$$

$$\Rightarrow \frac{C_{gin,j}}{C_{gin,j-1}} = \frac{C_{gin,j+1}}{C_{gin,j}}$$

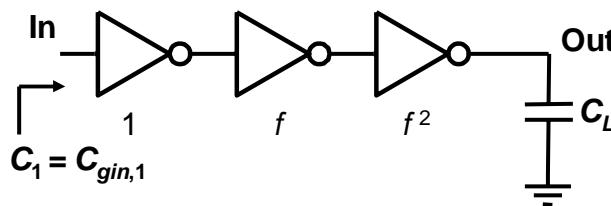
Load cap / input cap ratio
same for each stage

$$\Rightarrow f_j = \frac{C_{gin,j+1}}{C_{gin,j}} = N \sqrt{\frac{C_L}{C_{gin,1}}} = N/F$$

$F = C_L/C_{gin,1}$: path fan-out.
Same fan-out, same delay for
each stage.

$$\Rightarrow t_{p,j} = t_{p0} \left(1 + \frac{f_j}{\gamma} \right) = t_{p0} \left(1 + \frac{C_{gin,j+1}}{\gamma C_{gin,j}} \right) = t_{p0} \left(1 + \frac{N/F}{\gamma} \right)$$

Optimal Tapering for Fixed-N Summary



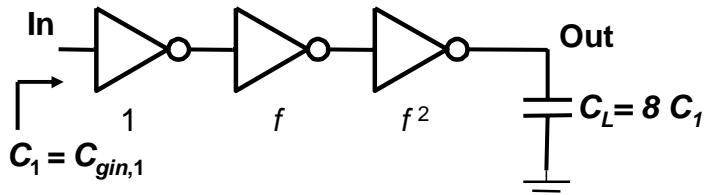
Delay per stage and total Path Delay

$$t_{p,j} = t_{p0} \left(1 + \frac{f_j}{\gamma} \right) = t_{p0} \left(1 + \frac{C_{gin,j+1}}{\gamma C_{gin,j}} \right) = t_{p0} \left(1 + \frac{N/F}{\gamma} \right)$$

$$t_p = N t_{p0} \left(1 + \frac{f_j}{\gamma} \right)$$

$$f_1 = f_2 = f_3 = \dots = F^{1/N} \quad f_1 \times f_2 \times f_3 \times \dots = F \quad F = C_L/C_{gin,1}$$

Example



C_L/C_1 has to be evenly distributed across $N = 3$ stages:

$$f = \sqrt[3]{8} = 2 \quad t_p = 3t_{p0} \left(1 + \frac{\sqrt[3]{8}}{\gamma} \right) = 9t_{p0} \quad \text{for } \gamma = 1$$

Optimum Number of Stages

For a given load, C_L and given input capacitance C_{in}
find optimal f if N is free (and possibly non-integer)

$$C_L = F \cdot C_{in} = f^N C_{in} \quad \text{with} \quad N = \frac{\ln F}{\ln f}$$

$$t_p = N t_{p0} \left(1 + \frac{f}{\gamma} \right) = \frac{t_{p0} \ln F}{\gamma} \left(\frac{\gamma}{\ln f} + \frac{f}{\ln f} \right)$$

$$\frac{\partial t_p}{\partial f} = \frac{t_{p0} \ln F}{\gamma} \cdot \frac{-\gamma/f + \ln f - 1}{\ln^2 f} = 0$$

$$\ln f = 1 + \frac{\gamma}{f}$$

$$f = \exp \left(1 + \frac{\gamma}{f} \right)$$

Closed-form solution
only for $\gamma = 0$

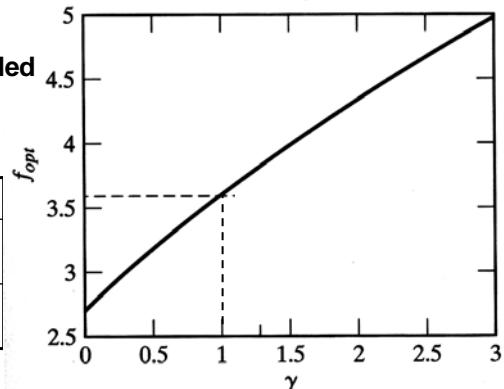
Optimum Effective Fanout f

Optimum f for given process defined by γ

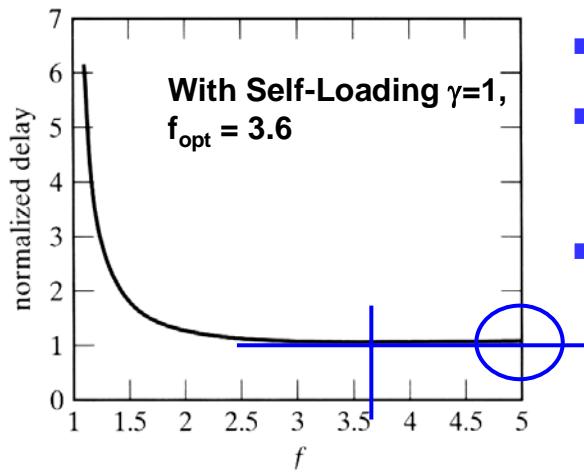
$$f = \exp\left(1 + \frac{\gamma}{f}\right) \quad N = \frac{\ln F}{\ln f}$$

(In practice, N must be rounded up or down to integer value)

	$\gamma=0$	$\gamma=1$
f_{opt}	e=2.72	3.6
N_{opt}	$\ln F$	$0.78\ln F$



Normalized t_p vs. f



- Slight increase of t_p for $f > f_{opt}$
- Choosing too few stages ($f > f_{opt}$) is relatively harmless for delay and saves area
- Too many stages is expensive in terms of delay

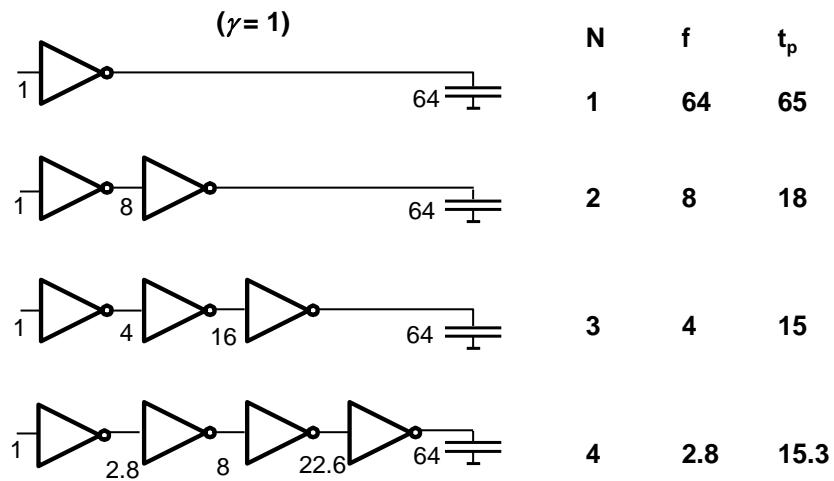
Fan-out of 4 (FO4) is safe common practice

Normalized delay function of F

$$t_p = N t_{p0} \left(1 + \frac{\sqrt{N/F}}{\gamma} \right) \quad (\gamma=1)$$

F	Unbuffered	Two Stage	Inverter Chain
10	11	8.3	8.3
100	101	22	16.5
1000	1001	65	24.8
10,000	10,001	202	33.1

Buffer Design



Power

■ **Dynamic Power**

■ **Static Power**

■ **Metrics**



www.quitpc.com



24 hours audio playback time

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CMOS Power Dissipation

- **Power dissipation is a very important circuit characteristic**
- **CMOS has relatively low static dissipation**
- **Power dissipation was the reason that CMOS technology won over bipolar and NMOS technology for digital IC's**
- **(Extremely) high clock frequencies increase dynamic dissipation**
- **Low V_T increase leakage**
- **Advanced IC design is a continuous struggle to contain the power requirements!**



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Power Density



Estimate

- Furnace: 2000 Watt, $r=10\text{cm}$ $\rightarrow P \approx 6\text{Watt/cm}^2$
- Processor chip: 100 Watt, 3cm^2 $\rightarrow P \approx 33\text{Watt/cm}^2$

Power-aware design, design for low power, is blossoming subfield of VLSI Design

Where Does Power Go in CMOS

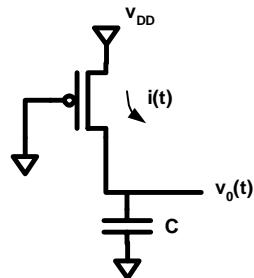
- Dynamic Power Consumption
 - Charging and discharging capacitors
- Short Circuit Currents
 - Short circuit path between supply rails during switching (NMOS and PMOS on together)
- Leakage
 - Leaking diodes and transistors
 - May be important for battery-operated equipment

Dynamic Power

Dynamic Power

- E_i = energy of switching event i
 - independent of switching speed
 - depends on process, layout
- Power = Energy/Time
$$P = \frac{1}{T} \sum_i E_i$$
- E_i = Power-Delay-Product P-D
 - important quality measure
- Energy-Delay-Product E-D
 - combines power*speed performance

Low-to-High Transition Energy

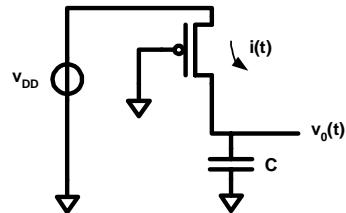


Equivalent circuit for low-to-high transition

E_C - Energy stored on C

$$\begin{aligned} E_C &= \int_0^\infty i v_0 dt \quad v_0 = v_0(t) \quad i = i(t) = C \frac{dv_0}{dt} \\ &= \int_0^\infty C v_0 \frac{dv_0}{dt} dt \\ &= \int_0^{V_{DD}} C v_0 dv_0 = \frac{1}{2} C v_0^2 \Big|_0^{V_{DD}} = \frac{1}{2} C V_{DD}^2 \end{aligned}$$

Low-to-High Transition Energy



$E_{V_{DD}}$ Energy delivered by supply

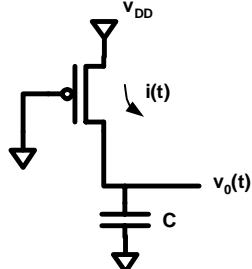
$$E_{V_{DD}} = \int_0^{\infty} i(t) V_{DD} dt = \int_0^{V_{DD}} CV_{DD} \frac{dv_0}{dt} dt = CV_{DD}^2$$

$$E_{V_{DD}} = CV_{DD}^2 \quad E_c = \frac{1}{2} CV_{DD}^2$$

Where is the rest?



Low-to-High Transition Energy

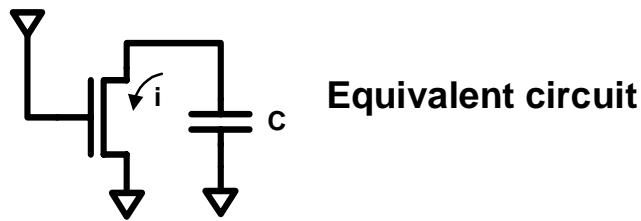


E_{diss} Energy dissipated in transistor

$$\begin{aligned} E_{diss} &= \int_0^{\infty} i(V_{DD} - v_0) dt \\ &= \int_0^{\infty} iV_{DD} dt - \int_0^{\infty} iv_0 dt \\ &= E_{V_{DD}} - E_c \end{aligned}$$



High-to-Low Transition Energy



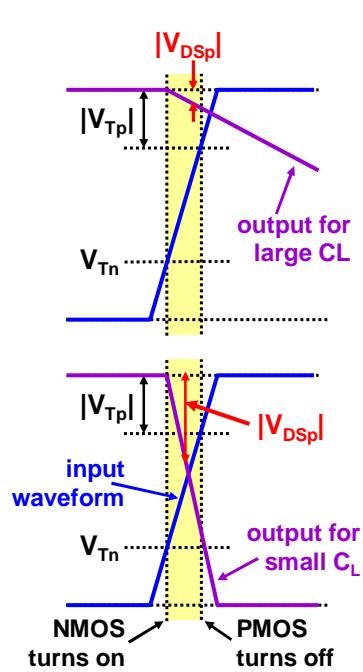
Equivalent circuit

Exercise: Show that the energy that is dissipated in the transistor upon discharging C from V_{DD} to 0 equals $E_{diss} = \frac{1}{2}CV_{DD}^2$

CMOS Dynamic Power Dissipation

$$\begin{aligned} \text{Power} &= \frac{\text{Energy}}{\text{Time}} = \frac{\text{Energy}}{\text{transition}} \times \frac{\#\text{transitions}}{\text{time}} \\ &= CV_{DD}^2 \times f \end{aligned}$$

- Independent of transistor on-resistances
- Can only reduce C , V_{DD} or f to reduce power



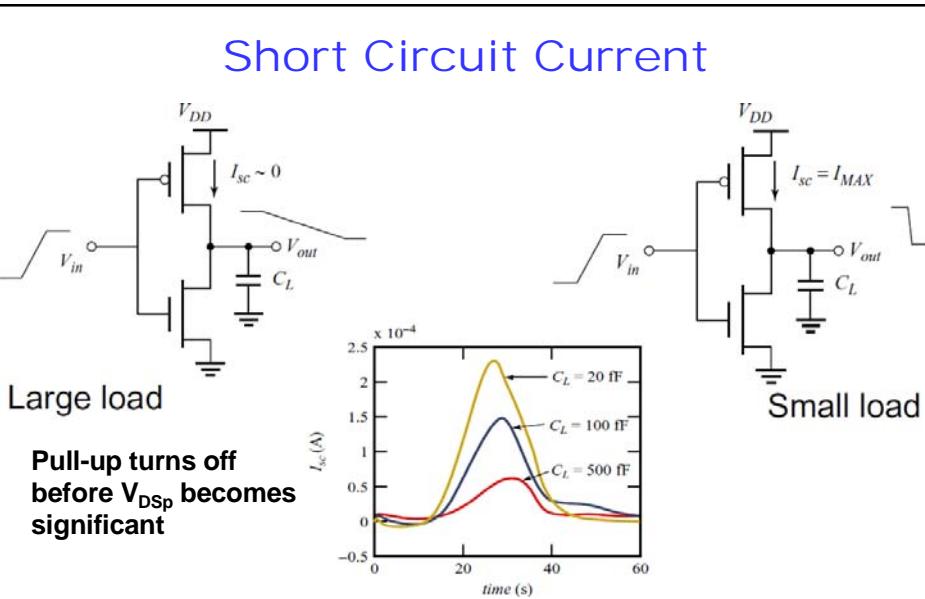
Short Circuit Current

- Input and output waveforms of inverter loaded with a large capacitance (top) and with a small capacitance (bottom).
- Shaded area is where both pull-up and pull-down transistors are on (this is when short-circuit current can exist). This region is determined by crossings of input waveform with V_{TN} and $V_{DD} - |V_{TP}|$.
- Short-circuit current increases with $|V_{DSP}|$. This is clearly much larger for small C_L compared to large C_L .
- Similarly, short-circuit current can exist for low-to-high transition at output.

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Best to maintain approximately equal input/output slopes

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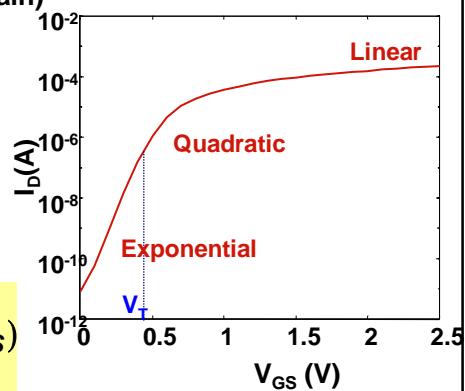
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Leakage

- Leakage current of reverse biased S/D junctions
- Sub-threshold current of MOS devices
- no channel → **parasitic bipolar device:**
n+ (source) – p (bulk) – n+ (drain)
- Important source of leakage



$$I_D = I_0 e^{\frac{qV_{GS}}{nkT}} \left(1 - e^{-\frac{qV_{DS}}{kT}} \right) (1 + \lambda \cdot V_{DS})$$



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Sub-Threshold Current

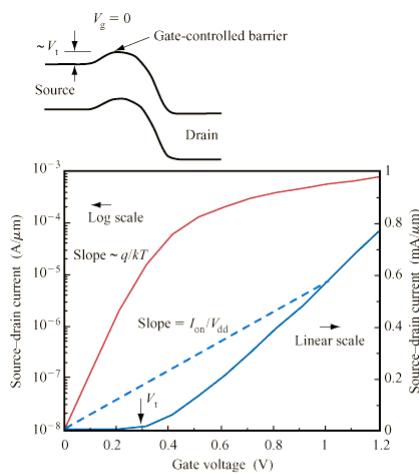


Figure 2

MOSFET current in both logarithmic (left) and linear (right) scales vs. gate voltage. The slope of the dotted line represents the large-signal transconductance for a digital circuit. Inset shows the band diagram of an n-MOSFET. The barrier height at $V_g = 0$ is proportional to V_t .

Y. Taur, CMOS design near the limit of scaling, IBMJRD, Volume 46, Numbers 2/3, 2002

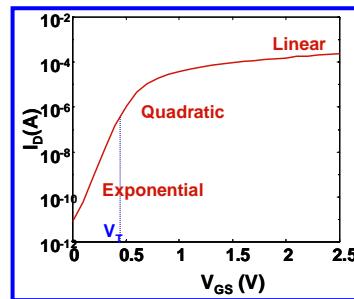
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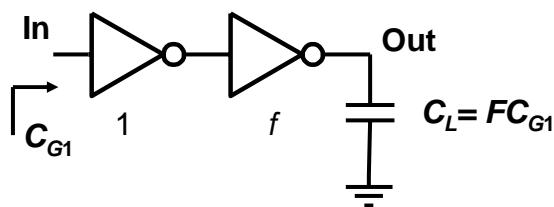
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Sub-Threshold Current

- Rapidly becomes bottleneck with lowering threshold voltages
- Modern technologies offer low- V_t and hi- V_t devices
Balance speed and power



Transistor Sizing for Minimum Energy



$$t_{pHL} \approx 0.52 \frac{C_L V_{DD}}{(W/L)_n k_n V_{DSATn} (V_{DD} - V_{Tn} - V_{DSATn}/2)}$$



$$t_p = t_{p0} \left(\left(1 + \frac{f}{\gamma} \right) + \left(1 + \frac{F}{f\gamma} \right) \right)$$

$$t_{p0} \propto \frac{V_{DD}}{V_{DD} - V_{TE}}$$

See Eq. 5.21

$V_{TE} = V_T - \frac{1}{2}V_{DSAT}$: Effective V_T

Transistor Sizing (2)

$$t_p = t_{p0} \left(\left(1 + \frac{f}{\gamma} \right) + \left(1 + \frac{F}{f\gamma} \right) \right) \quad t_{p0} \propto \frac{V_{DD}}{V_{DD} - V_{TE}}$$

Performance Constraint (with $\gamma = 1$):

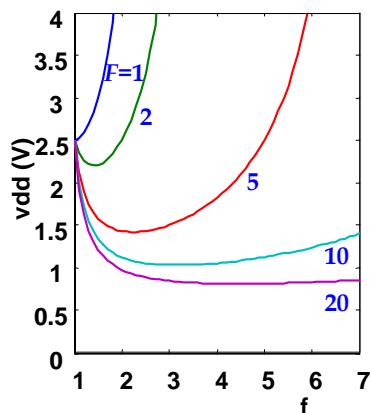
$$\frac{t_p}{t_{pref}} = \frac{t_{p0}}{t_{p0ref}} \frac{\left(2 + f + \frac{F}{f} \right)}{(3 + F)} = \left(\frac{V_{DD}}{V_{ref}} \right) \left(\frac{V_{ref} - V_{TE}}{V_{DD} - V_{TE}} \right) \frac{\left(2 + f + \frac{F}{f} \right)}{(3 + F)} = 1$$

- V_{TE} : technology (0.5 V), V_{ref} : standard supply (2.5 V)
- F : fanout
- V_{DD} , f : design parameters
- V_{DD} is a function of f , given a fixed performance

$$V_{DD} = \frac{f(15 + 5F)}{(14f - 8f^2 - 8F + 10fF)}$$

Transistor Sizing (3)

$V_{DD}=f(f)$



- Supply voltage needed as a function of f to maintain reference performance
- Lowest supply voltage needed for $f = F^{0.5}$

$$V_{DD} = \frac{f(15 + 5F)}{(14f - 8f^2 - 8F + 10fF)}$$

Transistor Sizing (4)

Energy for single Transition:

$$E = V_{DD}^2 C_{g1} [(1+\gamma)(1+f) + F]$$

$$\frac{E}{E_{ref}} = \left(\frac{V_{DD}}{V_{ref}} \right)^2 \left(\frac{2+2f+F}{4+F} \right)$$

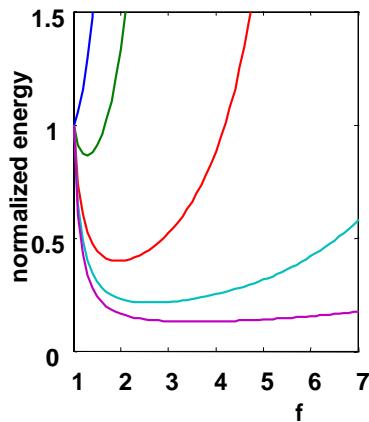
$$V_{DD} = \frac{f(15+5F)}{(14f-8f^2-8F+10fF)}$$

Size of 1st + 2nd inverter

$C_L = FC_{G1}$

Transistor Sizing (5)

$$E/E_{ref} = f(f)$$



$$\frac{E}{E_{ref}} = \left(\frac{V_{DD}}{V_{ref}} \right)^2 \left(\frac{2+2f+F}{4+F} \right)$$

- Device sizing is effective
- Oversizing is expensive for power
- Optimal sizing for energy slightly different from sizing for performance

Technology Scaling

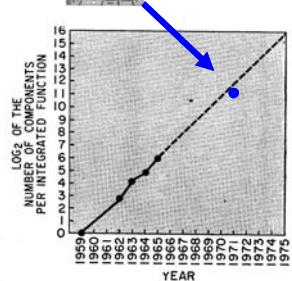
Also see: IBM JRD, Vol 46, no 2/3, 2002

Scaling CMOS to the limit

<http://www.research.ibm.com/journal/rd46-23.html>



Moore's Law



The number of transistors that can be integrated on a single chip will double every 18 months

Gordon Moore, co-founder of Intel
[Electronics, Vol 38, No. 8, 1965]



Why Scaling

- **Reduce price per function:**
 - Want to sell more functions (transistors) per chip for the same money → better products
 - Build same products cheaper, sell the same part for less money → larger market
 - Price of a transistor has to be reduced
- But also want to be faster, smaller, lower power

Scaling Models

Fixed Voltage Scaling

- most common model until 1990's
- only dimensions scale, voltages remain constant

Full Scaling (Constant Electrical Field)

- ideal model — dimensions and voltage scale together by the same factor S

General Scaling

- most realistic for today's situation —
- voltages and dimensions scale with different factors

Scaling for Velocity Saturated Devices

Constant Field Scaling: $S = U$

Parameter	Relation	General Scaling
W, L, t_{ox}		$1/S$
V_{DD}, V_T		$1/U$
N_{SUB}	V / W_{dep}^2	S^2/U
Area / Device	WL	$1/S^2$
C_{ox}	$1/t_{ox}$	S
C_{gate}	$C_{ox} WL$	$1/S$
k_n, k_p	$C_{ox} W/L$	S
I_{sat}	$C_{ox} W V$	$1/U$
Current Density	$I_{sat} / Area$	S^2/U
R_{on}	V / I_{sat}	1
Intrinsic Delay	$R_{on} C_{gate}$	$1/S$
Power / Device	$I_{sat} V$	$1/U^2$
Power Density	$P / Area$	S^2/U^2

IC Technology Scaling

Scaling improves density and **performance**

- First order **scaling theory** 2008 / 1971
- dimensions, $1/S$ 0.007
- voltages $1/S$ 0.007
- intrinsic delay $1/S$ 0.007
- power per transistor $1/S^2$ 0.00004

- **Scaling trend**



Technology Practice & ITRS

- Scaling – Technology Generations
- $S \approx 1.4 \approx 2^{0.5}$ per generation
- ... – 250 – 180 – 130 – 90 – 65 – 45 – 35 – 22 – ... nm
- ITRS: International Technology Roadmap for Semiconductors
Industry-wide organization for forecasting technology developments – and (planning) requirements



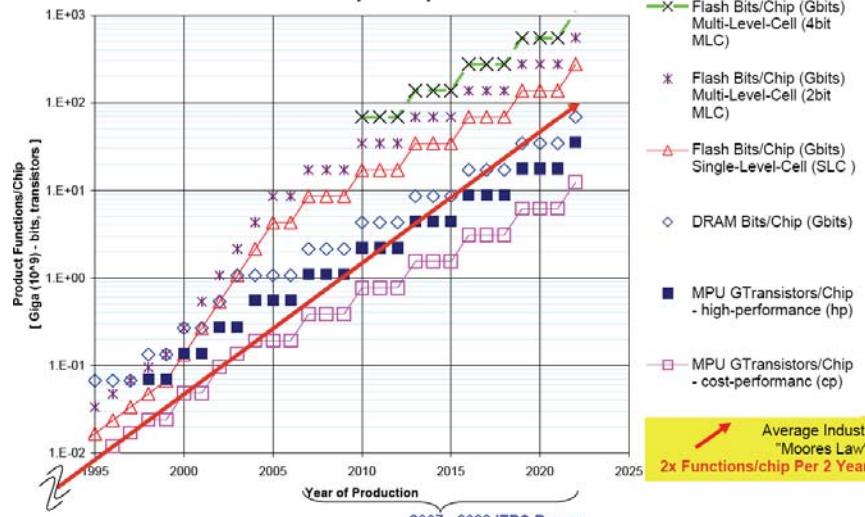
<http://www.itrs.net/home.html>

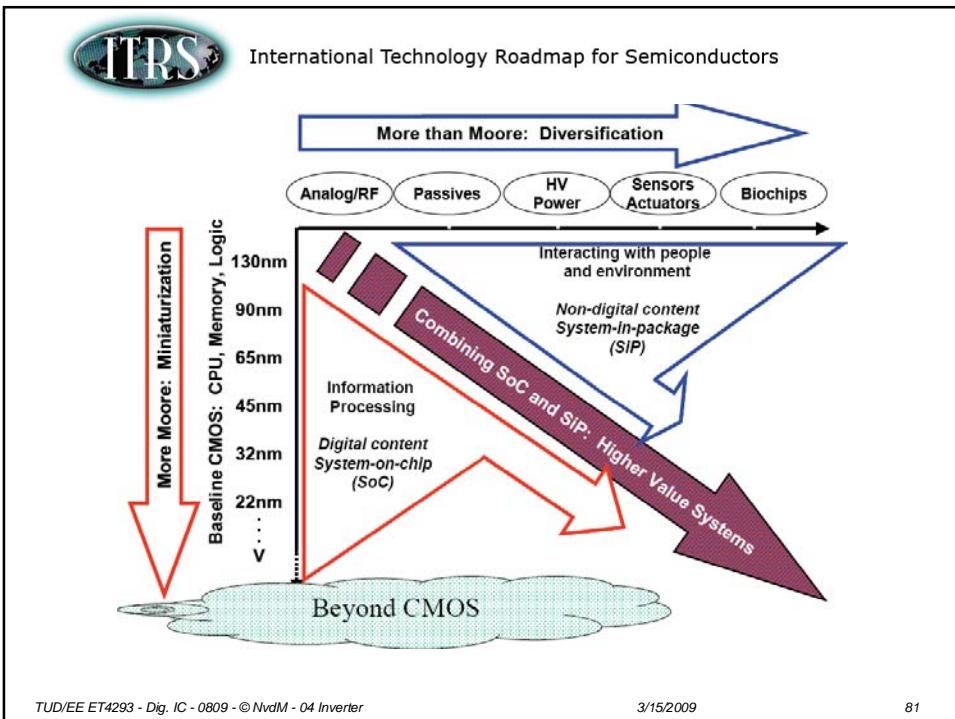
Not really – it is more like science
(and a self-fulfilling prophecy at the same time)



International Technology Roadmap for Semiconductors

2007 ITRS Product Technology Trends -
Functions per Chip





Summary

- Digital Gate Characterization (§ 1.3)
- Static Behavior (Robustness) (§ 5.3)
 - VTC
 - Switching Threshold
 - Noise Margins
- Dynamic Behavior (Performance) (§ 5.4)
 - Capacitances
 - Delay
- Power (§ 5.5)
 - Dynamic Power, Static Power, Metrics
- Scaling (§ 5.6)